

ADMETA 2017 AWARD NOTICE

Oct. 12, 2018

The committee of Advanced Metallization Conference 2017 Asian Session has decided, following the evaluation process, give this year's awards to the following papers:

ADMETA Award

Authors: ○R. Ifuku¹, T. Matsumoto¹, T. Sakai², and A. Kajita² [¹Tokyo Electron, ²Toshiba]

Paper Title: Catalyst-free Growth of Graphene on 300 mm Dielectric Substrate by Microwave Plasma Enhanced Chemical Vapor Deposition at Low Temperatures

Paper Number: 6-3

Technical Achievement Award

Authors: K. Miyano, M. Tsukui, H. Nago, Y. Iyechika, T. Kobayashi, Y. Ishikawa, H. Takahashi, S. Mitani, and T. Yoda (NuFlare Technology)

Paper Title: The Origin and Suppression of Critical Deep-Pit in the HEMT Structure Using GaN on Si Technology with Strained Layer Super Lattice

Paper Number: 6-2

Poster Award

Authors: ○Y. Mizushima^{1,2}, Y. Kim², S. Kodama², T. Nakamura², and T. Ohba² [¹Fujitsu Laboratories, ²Tokyo Institute of Technology]

Paper Title: Plan view stress distribution at 1 μm underneath of DRAM device using WOW ultra-thinning technology

Paper Number: P-16

An award ceremony was held at the ADMETA^{Plus} 2018.